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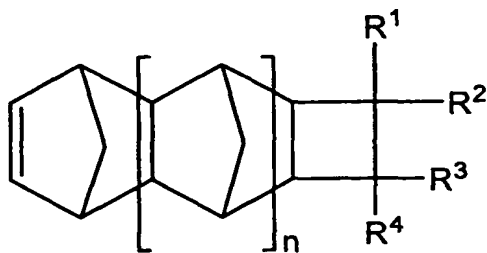
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(54) Title: PHOTORESISTS, FLUOROPOLYMERS AND PROCESSES FOR 157 NM MICROLITHOGRAPHY



(I)

(57) **Abstract:** The invention provides a polymer having (a) at least one repeat unit derived from an ethylenically unsaturated compound having at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom; and (b) at least one repeat unit derived from an ethylenically unsaturated cyclic compound of structure: (I) wherein n is 0, 1, or 2; and R<sup>1</sup> to R<sup>4</sup> are independently H; C<sub>1</sub>-C<sub>10</sub> alkyl or alkoxy, optionally substituted by halogen or ether oxygens; or C<sub>6</sub>-C<sub>20</sub> aryl. These polymers can be used in making photoresist compositions and coated substrates.